IN THE CLAIMS

This listing of claims replaces all prior listings:

1. (Currently Amended) Method of manufacturing a diffusing reflector comprising the processes of:

preparing a substrate;

forming a first resin film having photosensitivity on said substrate;

providing gathering of pillar-shaped bodies isolated from each other through patterning of said resin film with photolithography;

deforming gently said pillar-shaped bodies through a reflow;

forming an uneven surface layer having the maximum inclination angle of under 12⁰ by coating with a thin layer of a second resin said gently deformed pillar-shaped bodies and covering with [[a]] the second resin open flat spaces located between said isolated pillar-shaped bodies to form one concave gap between two adjacent isolated pillar-shaped bodies so that upper end portions of said two adjacent isolated pillar-shaped bodies are higher than a lower end portion of said one concave gap in the thickness direction of the diffusing reflector, thereby minimizing an occurrence of a flat surface area on said substrate; and

forming a metal film on said uneven surface layer.

- 2. (Original) Method of manufacturing a diffusing reflector as claimed in claim 1, wherein said maximum inclination angle is about 10^{0} .
 - 3. (Cancelled).
- 4. (Previously Presented) Method of manufacturing a diffusing reflector as claimed in claim 1, wherein said reflow process is a heat treatment under the temperature of about 220°C.
- 5. (Previously Presented) Method of manufacturing a diffusing reflector as claimed in claim 1, wherein gathering of polygonal pillar-shaped bodies isolated each other by the divided patterning of said first resin film by said photolithography is provided.

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6. (Previously Presented) Method of manufacturing a diffusing reflector as claimed in claim 5, wherein said first resin film is patterned by the divided patterning means so that size of gap between said polygonal pillar-shaped bodies isolated each other is almost equal to a minimum resolution of photolithography.